

Unit 8 - Week 6

Course outline

How does an NPTEL online course work?

Week 0

Week 1

Week 2

Week 3

Week 4

Week 5

Week 6

Quiz : Assignment 6

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Assignment 6

The due date for submitting this assignment has passed.
As per our records you have not submitted this assignment.

Due on 2020-03-25, 23:59 IST.

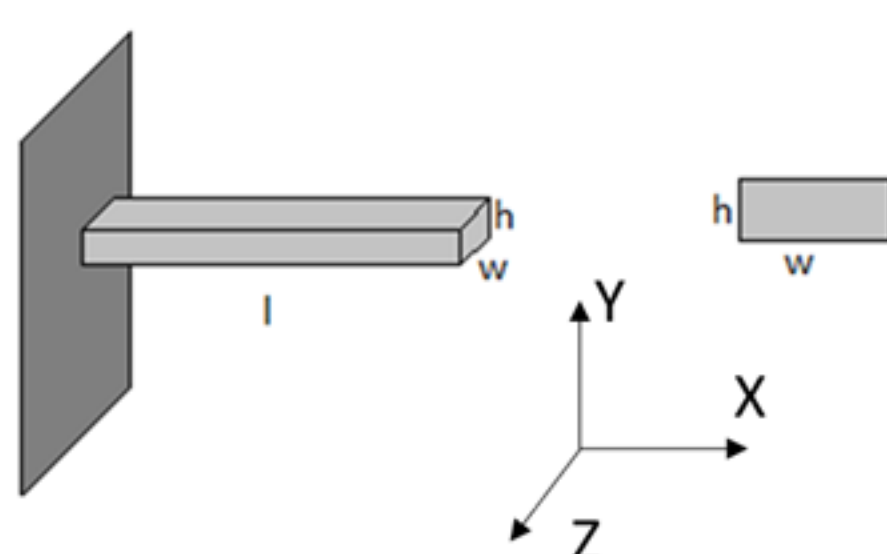
1) Consider a cantilever beam of length l , width b , and depth h made of a material with Young's modulus Y . It has a fundamental natural frequency f_1 . **2 points**
After scaling the width to αb and depth to βh , its natural frequency changes to f_2 . Calculate the ratio of these frequencies ($f_1 : f_2$), if values of α and β are 10^{-3} and 10^{-4} respectively. You can use, frequency, $f = \frac{1}{2\pi} \sqrt{\frac{k}{m}}$ where, k is stiffness and m is effective mass of the beam. Again, $m = cm_b$, where, c is a constant and m_b is actual mass of the beam. You can also consider only transverse vibration

- 10^{-1}
 10^{-2}
 10^4
 10^3

No, the answer is incorrect.
Score: 0

Accepted Answers:
 10^4

2) Consider a beam made of polysilicon with $Y=170$ GPa as shown in figure having length $100 \mu\text{m}$, width $10 \mu\text{m}$ and height $15 \mu\text{m}$. A proof mass of $50 \mu\text{g}$ is attached to its free end resulting in guided beam kind of motion. An acceleration is applied i) in Y-direction 12 m/s^2 and ii) in Z-direction (i.e., perpendicular to the side face of the beam) 15 m/s^2 . If the spring constant for a guided beam is $\frac{12YI}{l^3}$, what will be the magnitude of the deflection produced in Y and Z direction, respectively? All symbols have usual meaning. **2 points**



- i) $0.29 \mu\text{m}$, ii) $0.10 \mu\text{m}$
 i) 0.10 nm , ii) 0.29 nm
 i) $0.10 \mu\text{m}$, ii) $0.10 \mu\text{m}$
 i) $0.10 \mu\text{m}$, ii) $0.23 \mu\text{m}$
 i) $0.29 \mu\text{m}$, ii) $0.29 \mu\text{m}$
 i) 0.15 nm , ii) 0.23 nm

No, the answer is incorrect.
Score: 0

Accepted Answers:
i) 0.10 nm , ii) 0.29 nm

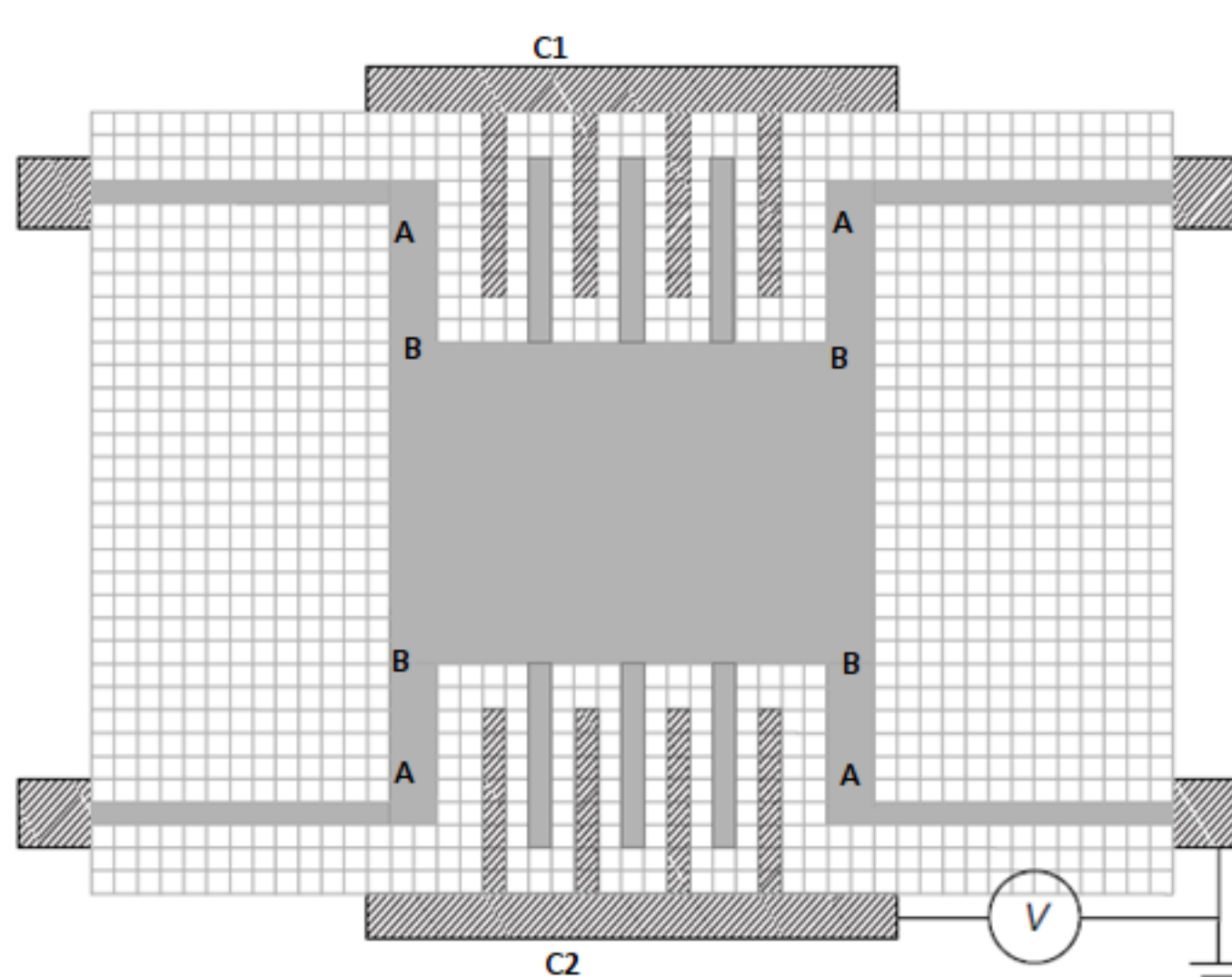
3) The electric energy density of a parallel plate capacitor (plate area A , gap between the plates d), if the electric field inside is E , is **1 point**

- $\frac{1}{2} \epsilon_0 E$
 $\frac{1}{2} \epsilon_0 E^2$
 $\frac{1}{2} \epsilon_0 E^2$
 $\frac{1}{2} \epsilon_0 E^3$

No, the answer is incorrect.
Score: 0

Accepted Answers:
 $\frac{1}{2} \epsilon_0 E^2$

4) The schematic of an in-plane accelerometer with a crab-leg suspension is shown below. Assume it is made of silicon whose Young's modulus is 169 GPa. The thickness everywhere is $25 \mu\text{m}$. Each square in grid has a size $5 \mu\text{m} \times 5 \mu\text{m}$. In order to perform a self-test, how much voltage needs to be applied to get a displacement of 5 nm ? (Deflection of beams AB is negligible and the top fixed comp C1 is not connected to circuit) **4 points**



Voltage = _____ V

No, the answer is incorrect.
Score: 0

Accepted Answers:
(Type: Range) 500,580

5) Which of the following processes will not avoid stiction? **1 point**

- Fabricating a stiff cantilever
 Using wider beam instead of narrow beam
 Using methanol for washing instead of water
 Making narrow dimples at the tip of cantilever
 Super-critical drying

No, the answer is incorrect.
Score: 0

Accepted Answers:
Using wider beams instead of narrow beam

6) Thickness of a $\langle 100 \rangle$ silicon wafer is $410 \mu\text{m}$. A square window of $1000 \mu\text{m}$ size is opened in the oxide on the front surface of the wafer with the mask edge aligned parallel to the $\langle 110 \rangle$ direction. The oxide on the back of the wafer is completely etched. This wafer is subjected to anisotropic etchant whose etch rate along the $\langle 100 \rangle$ direction is $50 \mu\text{m}/\text{hour}$. Due to this etching process for duration 4 hours, a square diaphragm of thickness $t \mu\text{m}$ and side $x \mu\text{m}$ has been created. Determine the diaphragm thickness t in _____ μm

No, the answer is incorrect.
Score: 0

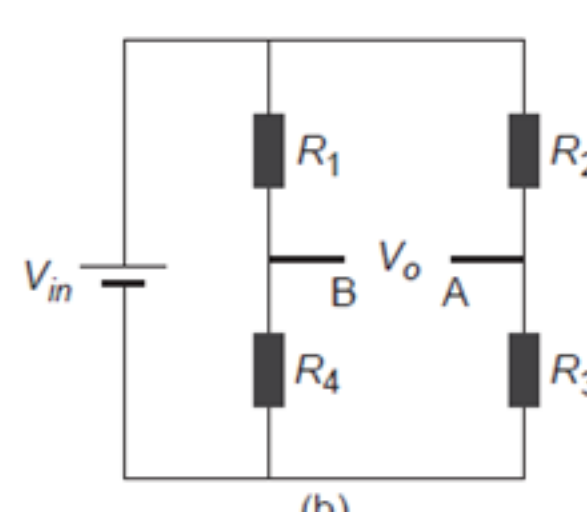
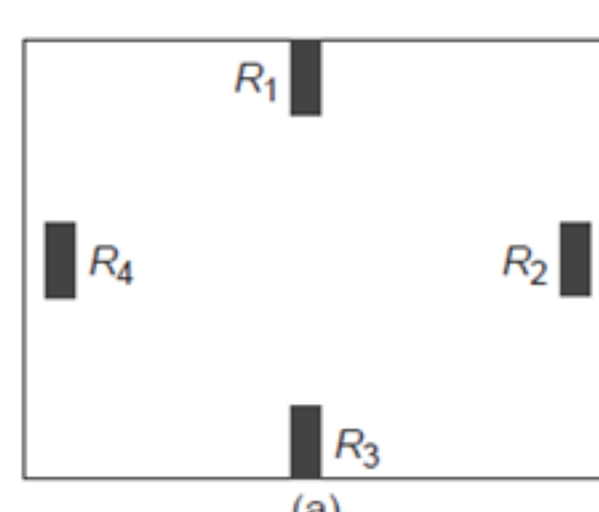
Accepted Answers:
(Type: Numeric) 10

7) With the data given in question number 6, determine diaphragm side x in _____ μm

No, the answer is incorrect.
Score: 0

Accepted Answers:
(Type: Range) 700,730

8) Polycrystalline p-type piezo-resistors R_1, R_2, R_3 , and R_4 , each of them equal to $R = 1 \text{ k}\Omega$, are arranged as shown in figure below on oxide grown on a single-crystal membrane having lateral dimensions $1 \text{ mm} \times 1 \text{ mm}$ and thickness $= 10 \mu\text{m}$. The polysilicon resistor has longitudinal gauge factor $G_L = 30$ and the transverse gauge factor G_T is negligibly small ($G_T = 0$). These resistors are connected in the form of a Wheatstone bridge as shown below. Assuming $v = 0$ and $Y = 150$ GPa for polysilicon, in this pressure sensor, what will be the sensitivity (in mV/Bar) for an input voltage of $V_{in} = 10 \text{ V}$? **2 points**



_____ mV/Bar

No, the answer is incorrect.
Score: 0

Accepted Answers:
(Type: Range) 490,510

9) The maximum stress a Si pressure sensor can withstand is 7 GPa. Pressure is applied on a square membrane of side $2a = 500 \mu\text{m}$ and thickness $h = 10 \mu\text{m}$. What should be the maximum operating range (in bar) of this pressure sensor for a safe application?

_____ bar

No, the answer is incorrect.
Score: 0

Accepted Answers:
(Type: Range) 20,25

2 points